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[Title of the Invention] MANUFACTURING METHOD OF LIQUID
CRYSTAL DISPLAY PANEL

[Abstract]

[Object] There is provided a manufacturing method of a liquid crystal display panel based on liquid crystal dropping method to manufacture the panel with high display quality and free from alignment error by sufficiently hardening UV curing resin that is used for adhering an extraction electrode substrate and a light shielding substrate.

[Solving Means] To manufacture a liquid crystal display panel, UV curing resin 81 is applied to the peripheral portion of the display area of a glass substrate 1 having an extraction electrode 42 formed of a metallic thin film or glass substrate 1 having a light shielding film 21 at the peripheral portion of the display area, and a predetermined amount of a liquid crystal material 7 is dropped on the display area of one of the substrates. Then, the two substrates are superposed and irradiated with ultraviolet rays from the glass substrate having the metallic extraction electrode 42 or from both sides of the two substrates, in order to harden the seal resin.

[Claims]

[Claim 1] A manufacturing method of a liquid crystal display panel, characterized by comprising the steps of:

applying UV curing resin to the peripheral portion of the display area of a glass substrate having an extraction electrode formed of a metallic thin film or glass substrate having a light shielding film at the peripheral portion of the display area;

dropping a predetermined amount of a liquid crystal material on the display area of one of the substrates;

superposing two substrates; and

irradiating ultraviolet rays from the glass substrate having the metal extraction electrode and thereby, hardening the seal resin.

[Claim 2] The method according to claim 1 is characterized in that the width of the extraction electrode in the area superposed by the UV curing seal resin is less than 40 μm , which is 2.5 times less than a distance to an adjacent extraction electrode.

[Claim 3] A manufacturing method of a liquid crystal display panel, characterized by comprising the steps of:

applying UV curing resin to the peripheral portion of the display area of a glass substrate having an extraction electrode formed of a metallic thin film or glass substrate having a light shielding film at the peripheral portion of the display area;

dropping a predetermined amount of a liquid crystal material on the display area of one of the substrates;

joining two substrates; and

irradiating ultraviolet rays from both sides of the two glass substrates and thereby, hardening the seal resin.

[Claim 4] The method according to claim 3 is characterized in that the width of the extraction electrode in the area superposed by the UV curing seal resin is less than 40 μm , which is 3.0 times less than a distance to an adjacent extraction electrode.

[Claim 5] A manufacturing method of a liquid crystal display panel, characterized by comprising the steps of:

applying UV curing resin to the peripheral portion of the display area of a glass substrate having an extraction electrode formed of a metallic thin film or glass substrate having a light shielding film made of black pigment-containing resin at the peripheral portion of the display area;

dropping a predetermined amount of a liquid crystal material on the display area of one of the substrates;

superposing two substrates; and

irradiating ultraviolet rays from the glass substrate having the metal extraction electrode and thereby, hardening the seal resin.

[Claim 6] The method according to claim 7 is characterized

in that the width of the extraction electrode in the area superposed by the UV curing seal resin is less than 30 μm , which is 2.0 times less than a distance to an adjacent extraction electrode.

[Claim 7] A manufacturing method of a liquid crystal display panel, characterized by comprising the steps of:

applying UV curing resin to the peripheral portion of the display area of a glass substrate having an extraction electrode formed of a metallic thin film or glass substrate having a light shielding film made of black pigment-containing resin at the peripheral portion of the display area;

dropping a predetermined amount of a liquid crystal material on the display area of one of the substrates;

joining two substrates; and

irradiating ultraviolet rays from both sides of the two glass substrates and thereby, hardening the seal resin.

[Claim 8] The method according to claim 7 is characterized in that the width of the extraction electrode in the area superposed by the UV curing seal resin is less than 30 μm , which is 2.5 times less than a distance to an adjacent extraction electrode.

[Detailed Description of the Invention]

[0001]

[Technical Field of the Invention]

The present invention relates to a manufacturing method of a liquid crystal display panel, more specifically, to a joining method of two laminated glass substrates having liquid crystal sandwiched therebetween.

[0002]

[Description of the Related Art]

A related art will be explained in reference to Figs. 9 - 12. The assembly method of a liquid crystal display panel is largely divided into two types.

[0003]

A first assembly method is a vacuum pressure impregnation method, wherein glass substrates were joined and an empty cell as shown in Figs. 9 - 11 was assembled. The empty cell was made vacuous, and a liquid crystal material was injected (or poured) using the differential pressure between the vacuum pressure in the empty cell and atmospheric pressure. In case of the vacuum pressure impregnation, after upper and lower glass substrates 1 were joined and seal resin 8 was fully hardened, a liquid crystal material was injected between the two substrates. As an ingredient of the seal resin 8, a thermosetting resin or a UV curing resin can be selected depending on the configuration of a panel.

[0004]

In recent years, to keep abreast with the trend of small-sized liquid crystal display panels for sake of space saving, the seal resin 8 has been superposed on the light shielding film 2 of the peripheral portion of a display area as shown in Fig. 9 and Fig. 10. However, in case of using the thermosetting seal resin, the seal resin 8 can be sufficiently hardened regardless of a positional relation with the light shielding film 2. Most of liquid crystal display panels having been manufactured so far were assembled by this vacuum pressure impregnation method. In effect, this is the method for which condition examination progressed most.

[0005]

A second assembly method is a dropping method, wherein a liquid crystal material was dropped on one of the substrates, and then the other substrate was adhered thereto. Because the throughput of the panel formation is short and the usage efficiency of the liquid crystal material is high, this method is expected as a next-generation assembly method.

[0006]

However, since the liquid crystal material makes a direct contact with non-hardened seal resin, the liquid crystal alignment easily comes apart. Therefore, a UV curing seal resin material that can quickly stabilize the liquid crystal alignment as much as possible is used.

[0007]

[Problems to be Solved by the Invention]

As described above, when a liquid crystal display panel is manufactured based on a dropping method, a UV curing seal resin material is preferably used. However, to make the ultraviolet rays of sufficient energy be irradiated onto the seal resin, constraints are needed for the design of the peripheral portion of the display area of the panel and the UV irradiation method.

[0008]

Especially, for the liquid crystal display panel using metal extraction electrode, such as a TFT liquid crystal display panel or a reflective liquid crystal display panel using reflection by an electrode, there is always an area on the seal resin where sufficient ultraviolet rays are not irradiated no matter how good the UV irradiation is performed from all directions of the panel, and the liquid crystal alignment around the area is unstable because the seal resin is not hardened sufficiently.

[0009]

For this reason, to form the liquid crystal panel with the metal extraction electrode based on the dropping method, as shown in Fig. 12, it is necessary to apply the UV curing seal resin 81 to farther outside the light shielding film 2 at the peripheral portion of the display area, and to

irradiate ultraviolet rays 90 through the UV blocking mask 91 from the substrate side with the light shielding film 21. Since it becomes the shade of the metal extraction electrode 42 or the light-shielding film 2 in case the peripheral area 10 is reduced by superposing seal resin to the light shielding film 2 in the peripheral portion of the display area as shown in Fig. 9 and Fig. 10, seal resin 8 cannot be fully hardened.

[0010]

[Means for Solving the Problems]

In order to solve the above-mentioned problem, it is effective to set a limit on the distance between an extraction electrode and an adjacent electrode (the area where an electrode is not formed: inter-electrode width) by materials of a light shielding film, and irradiate ultraviolet rays from a substrate side having an extraction electrode or irradiate ultraviolet rays from both sides of two joined substrates.

[0011]

By setting a limit (or constraint) to the design of extraction electrode width and extraction inter-electrode width, the ultraviolet rays incident upon seal resin from inter-electrode through reflection from the surface of the light shielding film of an opposite substrate, multiple reflection by the surfaces of the light shielding film and

the electrode, and dispersion by a filler agent among sealing materials can also be fully irradiated on the shade area of an electrode. In addition, the chain reaction of a photo-initiator in seal resin helps the seal resin of the shade area of an electrode be fully hardened.

[0012]

[Embodiment of the Invention]

Fig. 1- Fig. 6 illustrates cross-sectional views of major parts of a TFT liquid crystal display panel according to one embodiment of the present invention. In the drawings, reference numeral 1 denotes a glass substrate, 13 denotes a metal extraction electrode substrate, 14 denotes a light shielding substrate, 21 denotes a metal light shielding film, 22 denotes a light shielding film made of resin, 31, 32 and 33 denote R, G and B color filters, respectively, 41 denotes an ITO, 42 a metal extraction electrode, 5 denotes an overcoat, 6 denotes an alignment film, 7 denotes a liquid crystal material, 71 denotes a spacer particle, 81 denotes an UV curing seal resin, 90 denotes ultraviolet rays, and 91 denotes an UV blocking mask.

[0013]

Fig. 1 - Fig. 3 illustrate the cases where the light shielding film 21 is formed of a thin film, and Fig. 4 - Fig. 6 illustrate the cases where the light shielding film 22 is made of a resin material containing the black pigment. Also,

the cross-sectional views in Fig. 1 - Fig. 6 illustrate the cases where ultraviolet rays 90 are irradiated from the extraction electrode substrate 13 and from the light shielding substrate 14, respectively.

[0014]

The extraction electrode width and the inter-electrode width (the width of an area where an electrode of adjacent inter-electrode is not formed) change according to the material of a light shielding material and the UV irradiation method (i.e., whether ultraviolet rays are irradiated from the extraction electrode substrate 13 or from both substrates 13, 14), and are limited as shown in Table 4 below.

[0015]

Moreover, if the irradiation energy of ultraviolet rays is greater than a predetermined level, the constraint is hardly influenced by the amount of energy of irradiated ultraviolet rays.

[0016]

Detailed embodiments of the present invention will now be described in reference to Fig. 7, Fig. 8, Table 1, Table 2-1, Table 2-2, Table 3 and Table 4.

[0017]

[Example 1]

Photoresist was applied to a Cr film deposited glass

substrate, and a Cr pattern substrate 10 of A-O in Fig. 7 and Table 1 was created through a series of processes including UV irradiation through a photo mask, development, etching and resist exfoliation. The Cr pattern has a similar composition (simulation extraction electrode 43) to the metal extraction electrode. When ultraviolet curing for hardening seal resin is performed in a post process, the Cr pattern is formed in order to make an area equivalent to the shade of the extraction electrode. The simulation electrode width 431 and the inter-electrode width 432 of the A-O are shown in Table 1.

[0018]

[Table 1]

| Pattern | Electrode width (μm) | Inter-electrode width ((μm)) | Electrode width/Inter-electrode |
|---------|-----------------------------------|---|---------------------------------|
| A | 5 | 10 | 0.5 |
| B | 10 | 10 | 1.0 |
| C | 15 | 10 | 1.5 |
| D | 20 | 10 | 2.0 |
| E | 25 | 10 | 2.5 |
| F | 30 | 10 | 3.0 |
| G | 40 | 10 | 4.0 |

| | | | |
|---|----|----|-----|
| H | 20 | 20 | 1.0 |
| I | 30 | 20 | 1.5 |
| J | 40 | 20 | 2.0 |
| K | 30 | 30 | 1.0 |
| L | 60 | 30 | 2.0 |
| M | 40 | 40 | 1.0 |
| N | 80 | 40 | 2.0 |
| O | 50 | 50 | 1.0 |

[0019]

A thermosetting resin made of epoxy resin was applied (or spread) to the Cr pattern substrates 10 using a spin coater at 200°C for two hours to form an overcoat 5. Next, an ITO 41 was formed thereon by sputtering, so that a total thickness of the film is in range from 2000Å to 2500Å. Then, the film was patterned in a stripe shape through photolithography, and a segment substrate 11 for use in STN liquid crystal display panels was formed (refer to Fig. 8).

[0020]

An alignment film 6 made of polymerized resin material was formed on the surfaces of the segment substrate 11 and a color filter substrate 12 having the common pattern of ITO prepared in advance, so that a thickness of the film is in range from 500Å to 1000Å. Later, a rubbing process was performed in a predetermined direction so that the film can

be assembled as a STN liquid crystal display panel. The light shielding film 2 is formed in this color filter substrate 12, and two types of light shielding films (one made of Cr and the other made of black pigment-containing resin) were prepared.

[0021]

Next, the UV curing epoxy acrylate group seal resin 81 containing 1-2% of glass fiber with an average particle diameter of $7.0\mu\text{m}$ was applied to the peripheral portion of the display area of the segment substrate 11 through a screen print method. And, a predetermined amount of a liquid crystal material 7 was dropped at the display area. At this time, the seal resin 81 was formed in such a manner that it is superposed with the pattern of the simulation extraction electrode 43 formed by Cr and that it surrounds the display area.

[0022]

On the other hand, to the color filter substrate 12, 200-300 spacer particles 71 per square millimeter with an average particle diameter of $6.5\mu\text{m}$ made of resin having a fixing material were dispersed, and 150 times of heat treatments were performed in order to make sure the spacer particles are fixed to the substrate.

[0023]

Next, in a vacuum chamber, the segment substrate 11 and

the color filter substrate 12 were bonded in such a manner that the seal resin 81 is superposed on only a half of the light shield film 2 at the peripheral portion of the display area of the color filter substrate 12, and were taken from the vacuum chamber. Then, by irradiating ultraviolet rays 90 onto the seal resin 81, the STN liquid crystal display panel shown in Fig. 8 was formed. Here, the UV irradiation process was performed 5 minutes at 25mW/cm² (measured in 405nm), and ultraviolet rays were irradiated from the segment substrate 11 and the color filter substrate 12, respectively.

[0024]

After carrying out 130°C heat annealing to the STN liquid crystal display panels for 30 hours, a voltage was applied to the respective panels, and the stability of the alignment of liquid crystal was observed. The observation result is shown in Table 2-1 and Table 2-2.

[0025]

Next, for measurement of the degree of polymerization of seal resin, the panels A-O were disassembled, the seal resin 81 was removed, and FTIR analysis were performed. The measurement result is shown in Table 2-1 and Table 2-2.

[0026]

[Table 2-1]

| Pattern | Light shielding film | Alignment | | Degree of polymerization | |
|---------|----------------------------|--------------------------|----------------------------|-----------------------------|-------------------------------|
| | | UV (from one side) | UV (from both sides) | UV (from one side) | UV (from both sides) |
| A | Cr | O | O | 82.1 | 83.3 |
| B | Cr | O | O | 80.3 | 81.1 |
| C | Cr | O | O | 81.2 | 79.8 |
| D | Cr | O | O | 78.0 | 79.2 |
| E | Cr | O | O | 76.3 | 78.8 |
| F | Cr | Δ - O | O | 71.3 | 77.2 |
| G | Cr | X | Δ | 69.8 | 72.6 |
| H | Cr | O | O | 80.9 | 82.2 |
| I | Cr | O | O | 80.1 | 80.0 |
| J | Cr | O | O | 78.8 | 79.2 |
| K | Cr | O | O | 79.9 | 81.1 |
| L | Cr | X | X | 45.3 | 50.8 |
| M | Cr | O | O | 77.6 | 78.2 |
| N | Cr | X | X | 43.1 | 51.2 |
| O | Cr | X | X | 58.6 | 64.2 |

[0027]

[Table 2-2]

| Pattern | Light shielding film | Alignment | | Degree of polymerization | |
|---------|----------------------------|-----------------------------|-------------------------------|-----------------------------|-------------------------------|
| | | UV (from one side) | UV (from both sides) | UV (from one side) | UV (from both sides) |
| A | Resin | O | O | 79.8 | 80.6 |
| B | Resin | O | O | 77.9 | 78.6 |
| C | Resin | O | O | 78.1 | 78.0 |
| D | Resin | O | O | 75.3 | 77.8 |
| E | Resin | Δ - O | O | 73.3 | 76.9 |
| F | Resin | Δ | Δ - O | 66.0 | 71.4 |
| G | Resin | X | X | 58.8 | 64.2 |
| H | Resin | O | O | 79.3 | 78.2 |
| I | Resin | O | O | 76.8 | 78.4 |
| J | Resin | X | X | 53.4 | 65.3 |
| K | Resin | O | O | 76.3 | 77.7 |
| L | Resin | X | X | 34.1 | 47.2 |
| M | Resin | X | Δ | 59.3 | 67.7 |
| N | Resin | X | X | 33.4 | 32.1 |
| O | Resin | X | X | 48.8 | 59.9 |

[0028]

[Example 2]

Using A and M (a light shielding film 2 made of Cr and

resin), the STN liquid crystal display panel shown in Fig. 8 was formed as in Example 1 among Cr pattern substrates 10 of Example 1. Then, different amounts of UV irradiation time, such as 1, 2, 3, 5 and 10 minutes, were set for hardening seal resin 81, and ultraviolet rays were irradiated from the segment substrate. After performing the heat annealing process at 140°C for 30 hours, the stability of liquid crystal alignment was evaluated. Later, the panel was disassembled and its degree of polymerization was measured for each seal resin, according to FTIR analysis. The result is shown in Table 3.

[0029]

[Table 3]

| Patter n | Light shieldin g film | Irradiatio n time (min) | Alignmen t | Degree of polymerizatio n |
|-------------|-----------------------------|-------------------------------|---------------|---------------------------------|
| A | Cr | 1 | X | 55.4 |
| A | Cr | 2 | Δ - O | 72.3 |
| A | Cr | 3 | O | 81.1 |
| A | Cr | 5 | O | 82.1 |
| A | Cr | 10 | O | 81.9 |
| M | Cr | 1 | X | 52.2 |
| M | Cr | 2 | Δ - O | 69.3 |

| | | | | |
|---|----|----|-------|------|
| M | Cr | 3 | 0 | 76.9 |
| M | Cr | 5 | 0 | 77.6 |
| M | Cr | 10 | 0 | 78.2 |
| A | Cr | 1 | X | 51.2 |
| A | Cr | 2 | Δ - O | 70.3 |
| A | Cr | 3 | 0 | 18.8 |
| A | Cr | 5 | 0 | 79.8 |
| A | Cr | 10 | 0 | 78.2 |
| M | Cr | 1 | X | 43.1 |
| M | Cr | 2 | X | 51.1 |
| M | Cr | 3 | X | 59.3 |
| M | Cr | 5 | X | 59.3 |
| M | Cr | 10 | X | 60.0 |

[0030]

Table 2-1 and Table 2-2 shows that the degree of hardening of UV curing seal resin 81 changes (i.e., differs), depending on the electrode width 431 of the metal simulation extraction electrode 43 and the inter-electrode width 432, and depending on the quality of the materials of the light shielding film 2 of the color filter substrate 12 and the UV irradiation methods (e.g., from which glass substrate are ultraviolet rays irradiated?). It is believed that all irradiated ultraviolet rays are parallel lights, and they are not always incident on the substrate surface at right

angles and contain many inclined light. Thus, the ultraviolet rays are reflected from the light shielding film 2 or from the metal simulation extraction electrode 43, and irradiate seal resin 81 in the shade of the simulation electrode 43 or the light shielding film 2.

[0031]

According to Table 3, when a small amount of irradiation energy of ultraviolet rays is greater than the predetermined value (25mW/cm^2 , 3 minutes), the irradiation energy of ultraviolet rays has almost no influence on the electrode width 431, the inter-electrode width 432, and the degree of seal hardening.

[0032]

From these results, the design condition of the extraction electrode in case of assembling the liquid crystal display panel using a metal extraction electrode through UV irradiated seal resin is determined as shown in Table 4.

[0033]

[Table 4]

| Opposite light shielding | UV irradiation direction | Electrode width (μm) | Electrode width/Inter- electrode |
|--------------------------------|--------------------------------|--------------------------------------|--|
|--------------------------------|--------------------------------|--------------------------------------|--|

| layer | | | width |
|-------|------------|-----------|------------|
| Metal | One side | ≤ 40 | ≤ 2.5 |
| Metal | Both sides | ≤ 40 | ≤ 3.0 |
| Resin | One side | ≤ 30 | ≤ 2.0 |
| Resin | Both sides | ≤ 30 | ≤ 2.5 |

[0034]

In this example, to check the stability of liquid crystal alignment, the STN liquid crystal display panel whose alignment is easily disturbed by insufficiently hardened seal resin. But the same hardening effect is obtained even though other liquid crystal display panels besides those of TN mode are used.

[0036]

[Effect of the Invention]

By setting a limit to the electrode width of the metal extraction electrode and the inter-electrode width, the dropping method can be used for manufacturing a liquid crystal display panel that has a compact peripheral portion of the display area with stable liquid crystal alignment.

[Brief Description of the Drawings]

[Fig.1]

Fig. 1 is a cross-sectional view of a major part of a liquid crystal display panel according to one embodiment of

the present invention (in which a light shielding film is a metal light shielding film, seal resin is superposed on a half thereof, and ultraviolet rays are irradiated from an extraction electrode substrate).

[Fig. 2]

Fig. 2 is a cross-sectional view of a major part of a liquid crystal display panel according to one embodiment of the present invention (in which a light shielding film is a metal light shielding film, seal resin is superposed on a half thereof, and ultraviolet rays are irradiated from an extraction electrode substrate and a light shielding substrate).

[Fig. 3]

Fig. 3 is a cross-sectional view of a major part of a liquid crystal display panel according to one embodiment of the present invention (in which a light shielding film is a metal light shielding film, seal resin is superposed on every part thereof, and ultraviolet rays are irradiated from an extraction electrode substrate).

[Fig. 4]

Fig. 4 is a cross-sectional view of a major part of a liquid crystal display panel according to one embodiment of the present invention (in which a light shielding film is a light shielding film made of resin, seal resin is superposed on a half thereof, and ultraviolet rays are irradiated from

an extraction electrode substrate).

[Fig. 5]

Fig. 5 is a cross-sectional view of a major part of a liquid crystal display panel according to one embodiment of the present invention (in which a light shielding film is a light shielding film made of resin, seal resin is superposed on a half thereof, and ultraviolet rays are irradiated from an extraction electrode substrate and a light shielding substrate).

[Fig. 6]

Fig. 6 is a cross-sectional view of a major part of a liquid crystal display panel according to one embodiment of the present invention (in which a light shielding film is a light shielding film made of resin, seal resin is superposed on every part thereof, and ultraviolet rays are irradiated from an extraction electrode substrate).

[Fig. 7]

Fig. 7 is a plane view of a major part of a liquid crystal display panel according to an example of the present invention.

[Fig. 8]

Fig. 8 is a cross-sectional view of a major part of the STN liquid crystal display panel prepared by an example of the present invention.

[Fig. 9]

Fig. 9 is a cross-sectional view of a major part of a liquid crystal display panel assembled by a related art vacuum pressure impregnation method (in which seal resin is superposed on every part of a light shielding film).

[Fig. 10]

Fig. 10 is a cross-sectional view of a major part of a liquid crystal display panel assembled by a related art vacuum pressure impregnation method (in which seal resin is superposed on a half of a light shielding film).

[Fig. 11]

Fig. 11 is a cross-sectional view of a major part of a liquid crystal display panel assembled by a related art vacuum pressure impregnation method (in which seal resin is not superposed on a light shielding film).

[Fig. 12]

Fig. 12 is a cross-sectional view of a major part of a liquid crystal display panel assembled by a related art vacuum pressure impregnation method (in which seal resin is not superposed on a light shielding film, and ultraviolet rays are irradiated from the light shielding substrate).

[Description of Reference Numerals]

- 1: glass substrate
- 2: light shielding film
- 5: overcoat
- 6: alignment film

7: liquid crystal material
8: seal resin
10: Cr pattern substrate
11: segment substrate
12: color filter substrate
13: extraction electrode substrate
14: light shielding substrate
21: metal light shielding film
22: light shielding film made of resin
31: color filter (R)
32: color filter (G)
33: color filter (B)
41: transparent electrode (ITO)
42: extraction electrode
43: simulation extraction electrode
71: spacer particle
81: UV curing seal resin
90: ultraviolet rays
91: UV blocking mask
431: electrode width
432: inter-electrode width

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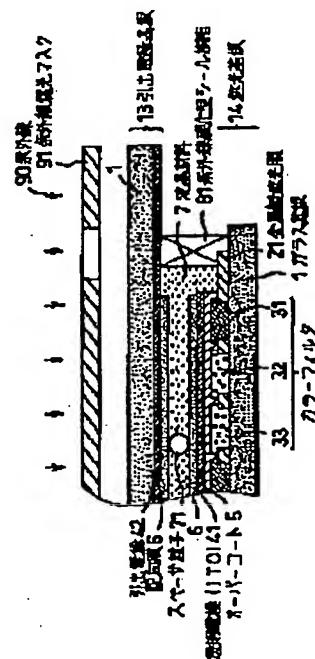
| | | | |
|----------|------------------|---------|---|
| (21)出願番号 | 特願平10-12703 | (71)出願人 | 000005821 松下電器産業株式会社 大阪府門真市大字門真1006番地 |
| (22)出願日 | 平成10年(1998)1月26日 | (72)発明者 | 炭田 社朗 大阪府門真市大字門真1006番地 松下電器 産業株式会社内 |
| | | (74)代理人 | 弁理士 松村 博 |
| | | | |

(54)【発明の名称】液晶パネルの製造方法

(57)【要約】

【課題】 液晶滴下工法による液晶パネルの製造方法で、引出電極基板と遮光基板とを接着する紫外線硬化型樹脂を十分に硬化し、配向異常のない表示品位の良好なパネルを製造する。

【解決手段】 金属薄膜で形成された引出電極42を有するガラス基板1と、表示領域周辺部に遮光膜21を有するガラス基板1の、どちらか一方の基板の表示領域周辺部に紫外線硬化型シール樹脂81を形成し、更にどちらか一方の基板の表示領域に所定量の液晶材料7を滴下した後、2枚の基板を重ね合わせて、金属製引出電極42を有するガラス基板側、または2枚の基板の両側から紫外線を照射してシール樹脂を硬化する。



【特許請求の範囲】

【請求項1】 金属薄膜で形成された引出電極を有するガラス基板と、表示領域周辺部に金属薄膜で形成された遮光膜を有するガラス基板のいずれか一方の基板の表示領域周辺部に紫外線硬化型シール樹脂を塗布し、更にいずれか一方の基板の表示領域に所定量の液晶材料を滴下した後、2枚の基板を重ね合わせ、金属製引出電極を有するガラス基板側から紫外線を照射してシール樹脂を硬化するガラス基板貼り合わせ工程を有することを特徴とする液晶パネルの製造方法。

【請求項2】 紫外線硬化型シール樹脂と重なる領域の引出電極の幅が $40\mu m$ 以下であり、更に隣接する引出電極との距離の2.5倍以下であることを特徴とする請求項1記載の液晶パネルの製造方法。

【請求項3】 金属薄膜で形成された引出電極を有するガラス基板と、表示領域周辺部に金属薄膜で形成された遮光膜を有するガラス基板のいずれか一方の基板の表示領域周辺部に紫外線硬化型シール樹脂を塗布し、更にいずれか一方の基板の表示領域に所定量の液晶材料を滴下した後、2枚の基板を貼り合わせ、2枚の基板の両側から紫外線を照射してシール樹脂を硬化するガラス基板貼り合わせ工程を有することを特徴とする液晶パネルの製造方法。

【請求項4】 紫外線硬化型シール樹脂と重なる領域の引出電極の幅が $40\mu m$ 以下であり、更に隣接する引出電極との距離の3.0倍以下であることを特徴とする請求項3記載の液晶パネルの製造方法。

【請求項5】 金属薄膜で形成された引出電極を有するガラス基板と、表示領域周辺部に黒色顔料を含んだ樹脂製の遮光膜を有するガラス基板のいずれか一方の基板の表示領域周辺部に紫外線硬化型シール樹脂を塗布し、更にいずれか一方の基板の表示領域に所定量の液晶材料を滴下した後、2枚の基板を重ね合わせ、金属製引出電極を有するガラス基板側から紫外線を照射してシール樹脂を硬化するガラス基板貼り合わせ工程を有することを特徴とする液晶パネルの製造方法。

【請求項6】 紫外線硬化型シール樹脂と重なる領域の引出電極の幅が $30\mu m$ 以下であり、更に隣接する引出電極との距離の2.0倍以下であることを特徴とする請求項5記載の液晶パネルの製造方法。

【請求項7】 金属薄膜で形成された引出電極を有するガラス基板と、表示領域周辺部に黒色顔料を含んだ樹脂製の遮光膜を有するガラス基板のいずれか一方の基板の表示領域周辺部に紫外線硬化型シール樹脂を塗布し、更にいずれか一方の基板の表示領域に所定量の液晶材料を滴下した後、2枚の基板を貼り合わせ、2枚の基板の両側から紫外線を照射してシール樹脂を硬化するガラス基板貼り合わせ工程を有することを特徴とする液晶パネルの製造方法。

【請求項8】 紫外線硬化型シール樹脂と重なる領域の

引出電極の幅が $30\mu m$ 以下であり、更に隣接する引出電極との距離の2.5倍以下であることを特徴とする請求項7記載の液晶パネルの製造方法。

【発明の詳細な説明】

【0001】

【発明の属する技術分野】本発明は、液晶パネルの製造方法に係り、特に、液晶を挟む二枚のガラス基板の貼り合わせ方法に関するものである。

【0002】

10 【従来の技術】従来の技術について図9～図12を用いて説明する。液晶パネルの組立方法は大きく分類して2通りの工法が提案されている。

【0003】まず第1の工法は、ガラス基板を貼り合わせて図9～図11に示すような空セルを組み立てた後に、空セル内を真空引きし、空セル内の真空圧と大気圧の圧力差を利用して液晶材料を注入する方法である（真空注入工法）。真空注入工法の場合には、上下2枚のガラス基板1を貼り合わせて、シール樹脂8を十分に硬化した後、液晶材料を注入する。シール樹脂8の材料として、パネル構成に応じて熱硬化型と紫外線硬化型を選択することができる。

【0004】近年、液晶パネルの省スペース化の要求に対して、図9、図10に示すような表示領域周辺部の遮光膜2にシール樹脂8が重なる構成が主流であるが、熱硬化型のシール樹脂を用いた場合には遮光膜2との位置関係に関わりなく、シール樹脂8を十分に硬化することができる。今までに生産された液晶パネルのほとんどがこの真空注入工法により組み立てられており、最も条件検討が進んだ工法である。

30 【0005】第2の工法は、液晶材料を一方の基板上に滴下した後、もう一方の基板を貼り合わせる工法（滴下工法）である。この工法はパネル作成のスループットが短く、液晶材料の利用効率も高いことから次世代の組立工法として期待されている。

【0006】しかし、未硬化のシール樹脂に液晶材料が直接接触するために液晶配向の乱れが発生しやすく、できるだけ液晶配向を安定させるために、迅速に硬化することのできる紫外線硬化型のシール樹脂材料が用いられている。

40 【0007】

【発明が解決しようとする課題】滴下工法により液晶パネルを製造する時には、上記のように紫外線硬化型のシール樹脂が用いられているが、この時十分なエネルギーの紫外線をシール樹脂に照射できるようにパネルの表示領域周辺部の設計及び紫外線照射方法に制約が必要となる。

【0008】特にTFT液晶パネルや電極による反射を用いた反射型液晶パネル等の、金属製の引出電極を用いた液晶パネルでは、パネルの上下いずれから紫外線照射を行ってもシール樹脂に紫外線を照射することができない。

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い領域が発生し、この領域近傍ではシール樹脂の硬化が不十分となり、液晶配向が安定しない。

【0009】このため滴下工法を用いて金属により引出電極が形成された液晶パネルを作成するためには、図12に示すように、表示領域周辺部の遮光膜2の更に外側に紫外線硬化型シール樹脂81を塗布して、遮光膜2のある基板側から紫外線遮光マスク91を通して紫外線90の照射を行う必要がある。図9、図10に示すような表示領域周辺部の遮光膜2にシール樹脂を重ねて、周辺領域を省スペース化する構成の場合には、金属製の引出電極42又は遮光膜2の陰となるために、シール樹脂8を十分に硬化することができないという問題があった。

【0010】

【課題を解決するための手段】上記課題を解決するために、遮光膜の材質毎に引出電極幅と、隣接する電極との距離（電極の形成されていない領域：電極間幅）に制限を設けて、引出電極を有する基板側から紫外線を照射することや、貼り合わせた2枚の基板の両側から紫外線を照射することが効果的である。

【0011】このように、引出電極幅と引出電極間幅の設計に制約を設けることによって、電極間からシール樹脂中に入射した紫外線を、対向基板の遮光膜表面での反射や遮光膜表面と電極表面による多重反射、更にはシール材料中のフィラー剤による散乱により、電極の陰領域にも十分に照射することができ、また、シール樹脂中の光開始剤の連鎖反応もあって、電極の陰領域のシール樹脂を十分に硬化することができる。

【0012】

【発明の実施の形態】図1～図6は本発明の実施の形態におけるTFT液晶パネルの主要部分の断面を示したものである。ここで、1はガラス基板、13は金属製の引出電極基板、14は遮光基板、21は金属製の遮光膜、22は樹脂製の遮光膜、31、32、33はそれぞれ赤、緑、青のカラーフィルタ、41は透明電極（ITO）。

| パターン | 電極幅(μm) | 電極間幅(μm) | 電極幅/電極間幅 |
|------|---------|----------|----------|
| A | 5 | 10 | 0.5 |
| B | 10 | 10 | 1.0 |
| C | 15 | 10 | 1.5 |
| D | 20 | 10 | 2.0 |
| E | 25 | 10 | 2.5 |
| F | 30 | 10 | 3.0 |
| G | 40 | 10 | 4.0 |
| H | 20 | 20 | 1.0 |
| I | 30 | 20 | 1.5 |
| J | 40 | 20 | 2.0 |
| K | 30 | 30 | 1.0 |
| L | 60 | 30 | 2.0 |
| M | 40 | 40 | 1.0 |
| N | 80 | 40 | 2.0 |
| O | 50 | 50 | 1.0 |

【0019】これらのCrパターン基板10にスピンドルーターを用いてエポキシ樹脂からなる熱硬化型樹脂を塗布、200°C、2時間の熱硬化を施してオーバーコート5を形成した。次に、スパッタリングによって透明電極（ITO）41を全面に2000～2500Åの膜厚と

0)、42は金属製の引出電極、5はオーバーコート、6は配向膜、7は液晶材料、71はスペーサー粒子、81は紫外線硬化型シール樹脂、90は紫外線、91は紫外線遮光マスクである。

【0013】図1～図3は遮光膜21としてCr等の金属薄膜を用い、図4～図6は遮光膜22として黒色顔料を含んだ樹脂製の遮光膜を用いた場合である。また図1～図6は、それぞれの断面図を用いて、紫外線90の照射を引出電極基板13側から照射した場合と、引出電極基板13と遮光基板14の両側から照射した場合を示している。

【0014】引出電極幅と、電極間幅（隣接する電極間の、電極が形成されていない領域の幅）には、遮光膜の材質と紫外線照射の方法（引出電極基板13側からか、両基板13、14側からか）によって異なり、（表4）のように制限されている。

【0015】また、紫外線の照射が一定エネルギー以上であれば、紫外線照射エネルギー量が上記制限に影響を及ぼすことはほとんど無い。

20 【0016】次に、本発明の具体的実施例について図7、図8、（表1）、（表2-1）、（表2-2）、（表3）、（表4）を用いて説明する。

【0017】（実施例1）Cr着膜済みのガラス基板にフォトレジストを塗布、フォトマスクを介しての紫外線照射、現像、エッチング、レジスト剥離等の工程を経て、図7及び（表1）に示すA～OのCrパターン基板10を作成した。このCrパターンは金属製の引出電極を模した構成（模擬引出電極43）となっており、後工程でシール樹脂硬化を行なうための紫外線硬化を行なう時

30 に、引出電極の陰に相当する領域を作り出すために形成したものである。このA～Oの模擬電極幅431と、電極間幅432は（表1）に示す通りである。

【0018】

【表1】

なるようにな成膜した後、フォトリソ法にてストライプ状にパターニングを行い、STN液晶パネル用のセグメント基板11を作成した（図8参照）。

【0020】これらのセグメント基板11と、予め準備しておいたITOのコモンパターン付のカラーフィルタ

基板12の表面に、ポリイミド樹脂製の配向膜6を500~1000Åの膜厚となるように形成した後、STN液晶パネルとして組み立てられるように、所定の方向にラビング処理を行った。このカラーフィルタ基板12には遮光膜2が形成されており、この遮光膜がCr製のものと、黒色顔料を含んだ樹脂製のものと2通り準備した。

【0021】次に、これらのセグメント基板11の表示領域周辺部に、平均粒径7.0μmのガラスファイバーを1~2%含んだ紫外線硬化型エポキシアクリレート系シール樹脂81をスクリーン印刷によって塗布し、更に、表示領域には所定量の液晶材料7を滴下した。この時シール樹脂81はCrによって形成した模擬引出電極43のパターンに重なるように、かつ表示領域を取り囲むように形成した。

【0022】一方、カラーフィルタ基板12には平均粒径6.5μmの接着材付樹脂製のスペーサ粒子71を平方ミリメートル当たり200~300個散布し、150度の熱処理を施して基板に接着した。

【0023】次に、真空チャンバー内でこれらのセグメ

ント基板11とカラーフィルタ基板12を、シール樹脂81がカラーフィルタ基板12の表示領域外周邊遮光膜2に半分だけ重なるように貼り合わせ、真空チャンバーから取り出した後にシール樹脂81に紫外線90を照射して、図8に示すSTN液晶パネルを作成した。この時紫外線90の照射は25mW/cm²(405nmにて測定)を5分間行い、セグメント基板11側から照射したものとセグメント基板11とカラーフィルタ基板12の両側から照射したものをそれぞれ作成した。

10 【0024】これらのSTN液晶パネルに130℃の熱アニールを30時間施した後にパネルに電圧印加して液晶の配向の安定性を観察した。観察結果を(表2-1), (表2-2)に示す。

【0025】次に、これらの作成したA~Oのパネルを分解して、シール樹脂81を剥がして、FTIR解析を行い、シール樹脂の重合度を測定した。測定結果を(表2-1), (表2-2)に示す。

【0026】

【表2-1】

| パターン | 遮光膜 | 耐向性 | | 重合度 | |
|------|-----|------|------|------|------|
| | | UV片面 | UV両面 | UV片面 | UV両面 |
| A | Cr | ○ | ○ | 82.1 | 83.3 |
| B | Cr | ○ | ○ | 80.3 | 81.1 |
| C | Cr | ○ | ○ | 81.2 | 79.8 |
| D | Cr | ○ | ○ | 78.0 | 79.2 |
| E | Cr | ○ | ○ | 78.8 | 78.8 |
| F | Cr | △ | ○ | 71.3 | 77.2 |
| G | Cr | × | ○ | 69.8 | 72.6 |
| H | Cr | ○ | ○ | 80.9 | 82.2 |
| I | Cr | ○ | ○ | 80.1 | 80.0 |
| J | Cr | ○ | ○ | 78.8 | 79.2 |
| K | Cr | ○ | ○ | 79.8 | 81.1 |
| L | Cr | ○ | ○ | 45.3 | 50.6 |
| M | Cr | ○ | ○ | 77.6 | 78.2 |
| N | Cr | ○ | ○ | 48.1 | 51.8 |
| O | Cr | × | ○ | 58.6 | 64.5 |

【0027】

【表2-2】

| パターン | 遮光膜 材料 | 耐向性 | | 重合度 | |
|------|-----------|------|------|------|------|
| | | UV片面 | UV両面 | UV片面 | UV両面 |
| A | Cr | ○ | ○ | 79.8 | 80.6 |
| B | Cr | ○ | ○ | 77.9 | 78.6 |
| C | Cr | ○ | ○ | 78.1 | 78.0 |
| D | Cr | △ | ○ | 75.8 | 77.8 |
| E | Cr | △ | ○ | 73.8 | 76.9 |
| F | Cr | △ | ○ | 66.0 | 71.4 |
| G | Cr | △ | ○ | 58.8 | 64.2 |
| H | Cr | △ | ○ | 70.3 | 76.2 |
| I | Cr | ○ | ○ | 78.8 | 78.4 |
| J | Cr | ○ | ○ | 53.4 | 65.2 |
| K | Cr | ○ | ○ | 76.3 | 77.7 |
| L | Cr | ○ | ○ | 34.1 | 47.2 |
| M | Cr | ○ | ○ | 59.3 | 67.7 |
| N | Cr | ○ | ○ | 55.4 | 82.1 |
| O | Cr | ○ | ○ | 48.6 | 59.9 |

【0028】(実施例2)実施例1で作成したCrパターン基板10のうち、A, M(遮光膜2がCr、樹脂共)を用いて実施例1と同様に図8のSTN液晶パネルを作成した。この際、シール樹脂81の硬化時の紫外線照射時間を1, 2, 3, 5, 10分とし、照射はセグメ

ント基板側から行った。これらのパネルに140℃、30時間の熱アニールを施して液晶配向の安定性を評価した後に、パネルを分解して、それぞれのシール樹脂をFTIR解析によって重合度を測定した。この結果を(表3)に示す。

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【0029】

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【表3】

| パターン | 遮光膜 | 照射時間(分) | 配向性 | 重合度 |
|------|------|---------|-----|------|
| A | C r | 1 | X | 55.4 |
| AA | C Cr | 2 | △~○ | 72.3 |
| AAA | C Cr | 3 | ○○ | 81.1 |
| AAA | C Cr | 5 | ○○ | 82.1 |
| AM | C Cr | 10 | ○○ | 81.9 |
| MM | C Cr | 12 | △~○ | 52.2 |
| MM | C Cr | 3 | ○○ | 69.3 |
| MM | C Cr | 3 | ○○ | 76.9 |
| MA | C Cr | 10 | ○○ | 77.6 |
| AA | 遮光膜 | 1 | ○○ | 78.2 |
| AA | 遮光膜 | 2 | △~○ | 51.2 |
| AA | 遮光膜 | 3 | ○○ | 70.3 |
| AA | 遮光膜 | 5 | ○○ | 78.8 |
| AM | 遮光膜 | 10 | ○○ | 79.8 |
| MM | 遮光膜 | 1 | ○○ | 78.2 |
| MM | 遮光膜 | 2 | ○○ | 43.1 |
| MM | 遮光膜 | 3 | ○○ | 51.1 |
| MM | 遮光膜 | 5 | ○○ | 58.3 |
| M | 遮光膜 | 10 | ○○ | 58.3 |

【0030】(表2-1)、(表2-2)から、金属製模擬引出電極43の電極幅431、電極間幅432によって紫外線硬化型シール樹脂81の硬化の度合が異なり、カラーフィルタ基板12の遮光膜2の材質と紫外線照射方法(どちらのガラス基板側から照射するか)によって異なっていることがわかる。これは、照射した紫外線は、すべて平行光で基板面に垂直に入射している訳ではなく、斜め光も多く含まれているために、遮光膜2や金属製模擬電極43によって反射されて模擬電極43や遮光膜2の陰となっている領域のシール樹脂81にも照射されるためであると考えられる。

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【0031】(表3)は、紫外線小照射エネルギーが一定値(2.5 mW/cm^2 , 3分)以上の場合には、紫外線小照射エネルギーは電極幅431、電極間幅432とシール硬化度にはほとんど影響がないことを示している。

【0032】これらの結果から、金属製の引出電極を用いた液晶パネルを紫外線照射型シール樹脂を用いて組み立てる場合の引出電極の設計条件が(表4)のように決定される。

【0033】
【表4】

| 対向遮光層 | UV照射方向 | 電極幅(μm) | 電極幅/電極間幅 |
|----------------------------|--------------------|----------------|-------------------|
| 金属 遮光 樹脂 遮光 樹脂 | 左 右 片面 両面 | 40 40 30 | 2.5 3.0 2.5 |
| | | | |
| | | | |

【0034】なお、本実施例では液晶配向の安定性を確認するために、シール樹脂の硬化が不十分な場合に、その影響で液晶配向が乱れやすいSTN液晶パネルを用いたが、TNモードその他の液晶パネルであっても、同様の硬化が得られる。

【0035】これらの結果をもとに、(表4)に示す条件通りにTFT液晶パネル(図1～図6)を作成し、液晶配向の安定した表示の良好なパネルであることを確認した。なお、これらの図では簡単のためにTFTアレイ等、本発明には直接関係しない部分の図示は省略した。

【0036】

【発明の効果】金属製引出電極の電極幅、電極間幅に制約を設けることによって、滴下工法を用いても、液晶配向が安定した表示領域周辺部がコンパクトな液晶パネルを製造することができる。

【図面の簡単な説明】

【図1】本発明の実施の形態における液晶パネルの主要部分の断面図(遮光膜が金属製遮光膜で、それにシール樹脂が半分重なり、紫外線は引出電極基板側から照射)

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【図2】本発明の実施の形態における液晶パネルの主要部分の断面図(遮光膜が金属製遮光膜で、それにシール樹脂が半分重なり、紫外線は引出電極基板及び遮光基板の両側から照射)

【図3】本発明の実施の形態における液晶パネルの主要部分の断面図(遮光膜が金属製遮光膜で、それにシール樹脂が全部重なり、紫外線は引出電極基板側から照射)

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【図4】本発明の実施の形態における液晶パネルの主要部分の断面図(遮光膜が樹脂製遮光膜で、それにシール樹脂が半分重なり、紫外線は引出電極基板側から照射)

【図5】本発明の実施の形態における液晶パネルの主要部分の断面図(遮光膜が樹脂製遮光膜で、それにシール樹脂が半分重なり、紫外線は引出電極基板及び遮光基板の両側から照射)

【図6】本発明の実施の形態における液晶パネルの主要部分の断面図(遮光膜が樹脂製遮光膜で、それにシール樹脂が全部重なり、紫外線は引出電極基板側から照射)

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【図7】本発明の具体的な実施例で用いた模擬電極パターンの主要部分の平面図

【図8】本発明の具体的実施例で作成したSTN液晶パネルの主要部分の断面図

【図9】従来技術における真空注入工法により組み立てた液晶パネルの主要部分の断面図（シール樹脂が遮光膜に全部重なる）

【図10】従来技術における真空注入工法により組み立てた液晶パネルの主要部分の断面図（シール樹脂が遮光膜に半分重なる）

【図11】従来技術における真空注入工法により組み立てた液晶パネルの主要部分の断面図（シール樹脂が遮光膜に重ならない）

【図12】従来技術における液晶滴下工法により組み立てた液晶パネルの主要部分の断面図（シール樹脂が遮光膜に重ならず、紫外線は遮光基板側から照射）

【符号の説明】

- 1 ガラス基板
- 2 遮光膜
- 5 オーバーコート
- 6 配向膜
- 7 液晶材料

8 シール樹脂

10 Crパターン基板

11 セグメント基板

12 カラーフィルタ基板

13 引出電極基板

14 遮光基板

21 金属製遮光膜

22 樹脂製遮光膜

31 カラーフィルタ（赤）

32 カラーフィルタ（緑）

33 カラーフィルタ（青）

41 透明電極（ITO）

42 引出電極

43 模擬引出電極

71 スペーサ粒子

81 紫外線硬化型シール樹脂

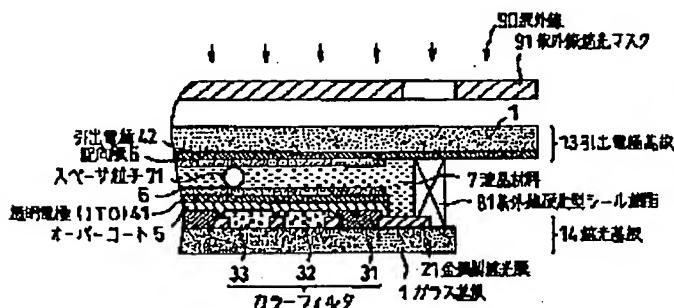
90 紫外線

91 紫外線遮光マスク

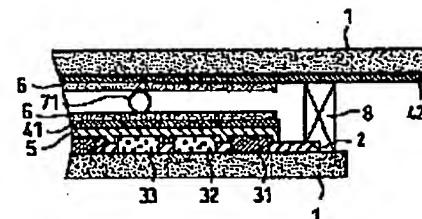
431 電極幅

20 432 電極間幅

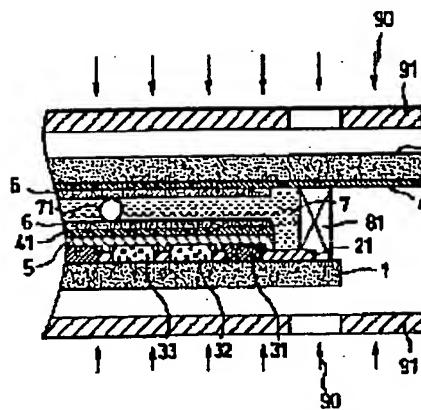
【図1】



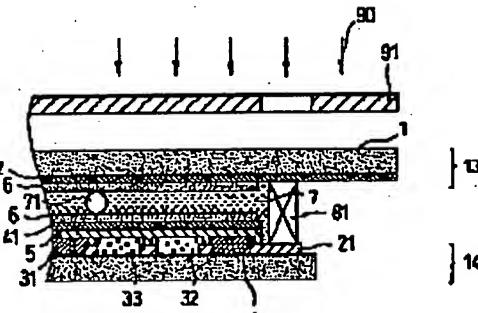
【図10】



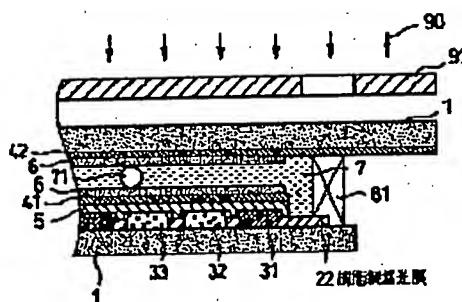
【図2】



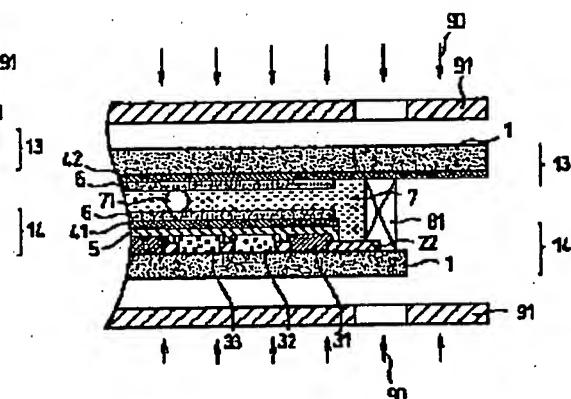
【図3】



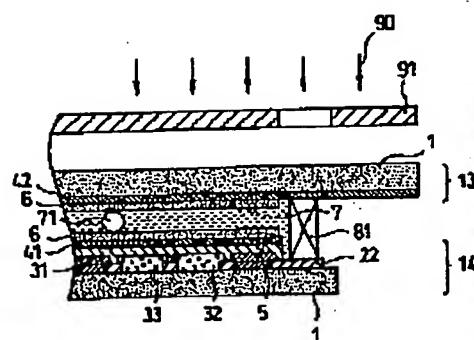
【図4】



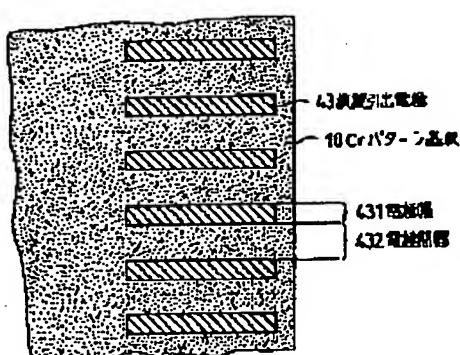
【図5】



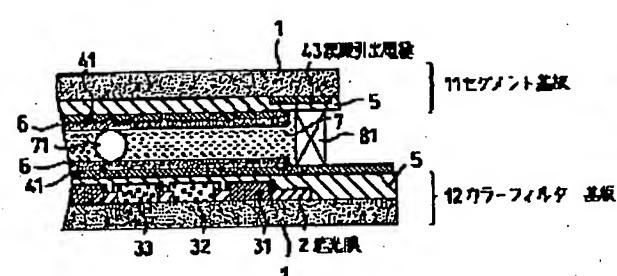
【図6】



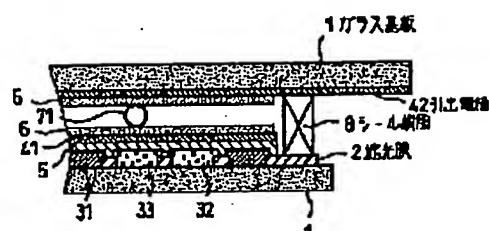
【図7】



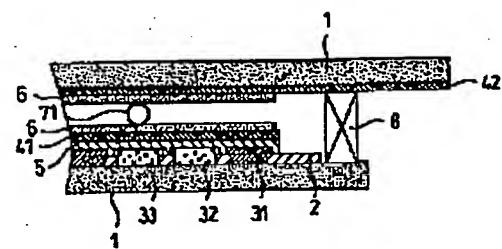
【図8】



【図9】



【図11】



【図12】

